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Thermal conductivity of Si–Ge-based nanostructures

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GEFÖRDERT VON



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Reduction in thermal conductivity

Cross-plane transport in $SL \rightarrow Coherent$ phonon scattering at interfaces

$$\kappa_{\rm ph} = \frac{1}{3}C\upsilon\ell$$

(*C* lattice heat capacity, v speed of sound, ℓ mean free path of phonons)



If layer thickness $a < \ell$, the thermal conductivity of the lattice κ_{ph} is reduced.

Phonon scattering

Superlattices, composites, quantum dot SLs, random multilayers



MD Simulation

[Frachioni, White: J Appl Phys 112 (2012) 14320]

MBE of Si-Ge layers

• Stack of alternating layers of Si and a $Si_{1-x}Ge_x$ alloy

Precision of single layers: ± 0.2 nm





Quantum dot Si-Ge superlattice

(001), (111) orientation of the Si substrate

◆ Si (111) → flat layers

◆ Si (100) → Ge islands (density ~ $10^9...10^{11}$ cm⁻²)



100 nm

AA Tonkikh *et al* Thin Sol Films (2011) doi: 10.1016/j.tsf.2011.10.049

3ω measurements

- ✦ Deposition of a 100 nm insulating Al₂O₃ layer by ALD
- Reference sample without the multilayer structure
- Differential 3ω measurement of the thermal conductivity of thin films, $U_{3\omega} = f(\kappa)$





Thin film thermal conductivity

1D heat flow

Measurement with one bolometer stripe, width $2b \gg d_{\rm f}$

 $\Delta T_{\rm f} \rightarrow 1D$ thermal conductivity $\kappa_{\rm 1D}$

2D heat flow

Measurements with two bolometer stripes, b_1 and b_2

 $\Delta T_{\rm f} \rightarrow$ in-plane thermal conductivity κ_{\parallel}

 \rightarrow cross-plane thermal conductivity κ_{\perp}



Bolometric temperature increase ΔT measured in a multilayer and a reference sample as a function of the frequency

Superlattices



Thermal conductivity of periodic SL



In-plane and cross-plane thermal conductivities for SLs with different Ge contents and periods

Random multilayers





1.2 nm Ge + 12 nm Si 1.2 nm Ge + 12 nm Si 1.8 nm Ge + 12 nm Si 0.9 nm Ge + 12 nm Si 1.6 nm Ge + 12 nm Si $6 \times , \approx 600$ nm



0.6 nm Ge + 4.1 nm Si 0.3 nm Ge + 5.1 nm Si 0.8 nm Ge + 4.8 nm Si 0.6 nm Ge + 5.7 nm Si 0.6 nm Ge + 3.8 nm Si $34 \times, \approx 940$ nm

Ge content

2.9 %

3.3 %

Results of random multilayers



Thermal conductivities in a random multilayer (2.9 % Ge) in comparison to a superlattice (3.5 % Ge).

Defect issues







[Watling, Paul: J Appl Phys 110 (2011) 114508]

Conclusions

- Lowest κ_{\perp} for SL with highest Ge content
- κ_⊥ a function of the SL period
 [cf. *e.g.* Rawat *et al*: J Appl Phys 105 (2009)
 024909]
- Only a small reduction in *κ*⊥ for random multilayers[↑] compared to SL[↑] observed due to low mass ratio in the multilayers investigated so far
 - → With higher Ge content,
 - 0.1 W K⁻¹m⁻¹ may be expected !
- Random multilayers exhibit a decrease in κ_{\parallel} by $\approx 50 \%$



[Frachioni, White: J Appl Phys **112** (2012) 14320]

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References

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